

adding a solvent for dilution to said first polishing liquid to form a second polishing liquid containing tetravalent cerium ions in a second concentration lower than the first concentration;

polishing a surface of a substrate containing Ru or a Ru compound in a surface region with the second polishing liquid,

wherein said addition of the solvent is carried out upon or immediately before the polishing of said substrate.

22. (Amended) A polishing method comprising:

preparing a first polishing liquid containing cerium (IV) nitrate in a first concentration;

adding a solvent for dilution to said first polishing liquid to form a second polishing liquid containing cerium (IV) nitrate in a second concentration lower than the first concentration;

polishing a surface of a substrate containing Ru or a Ru compound in a surface region with the second polishing liquid,

wherein said adding of the solvent is carried out upon or immediately before the polishing of said substrate.

--23. (New) A polishing method according to claim 17, wherein said solvent has a property of dissolving a solute of said first polishing liquid and does not substantially contain any solute.

24. (New) A polishing method according to claim 17, wherein said solvent consists essentially of water.

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